

Application No. 10/080,638  
Amendment

Customer No. 01933

Amendments to the Specification:

Please amend the paragraph at page 32, line 16 to page 33, line 13, as follows:

To state it concretely, as shown in FIG. 2(C), the ~~focus position with a depth of focus FZ (beam waist BW)~~ drawing position of an electron beam on the base material is adjusted and controlled to a pattern drawing position (pattern-drawing position) in one field ( $m=1$ ) of a unit space in the three-dimensional standard coordinate system. (This control is carried out, as described in the foregoing, by ~~any~~ at least one of the adjustment of the electric current value in the electron lens 16 to adjust the depth of focus FZ of the electron beam and adjustment of the drive control of the XYZ stage 30 or the both of them.) In addition, in this example, a field is set in such a way that the amount of height variation throughout one field is longer than the depth of focus FZ, but this invention is not limited to this. In this case, the depth of focus FZ represents, as shown in FIG. 14, the length of the range where the beam waist BW is effective in the electron beam B applied through the electron lens 16. Besides, in the case

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of the electron beam B, as shown in FIG. 14, with D put as the width of the electron lens 16 and f put as the depth up to the beam waist BW (a position where the beam waist is thinnest),  $D/f$  is about 0.01; further for example, the resolving power is of the order 50 nm, and the depth of focus is of the order several tens  $\mu\text{m}$ .